

Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

Claim 1 (currently amended): A sputtering target or thin film formed therefrom comprising a sputtering target or thin film made of a high purity hafnium material, wherein a zirconium content of the target or thin film is 1 to 1000wtppm, ~~and~~ a purity of the target or thin film is ~~4N~~ 4N5 to 6N excluding gas components of carbon, oxygen and nitrogen, and the contents of oxygen being 500wtppm or less, nitrogen and carbon being respectively 100wtppm or less, and iron, chromium and nickel being respectively 10wtppm or less.

Claims 2-26 (canceled).

Claim 27 (previously presented): A sputtering target or thin film according to claim 1, wherein said purity of the target or thin film is 4N5.

Claim 28 (previously presented): A sputtering target or thin film according to claim 1, wherein said purity of the target or thin film is 6N.

Claim 29 (canceled).

Claim 30 (new): A hafnium sputtering target comprising:

a sputtering target body consisting of high purity hafnium of a purity of at least

4N5 (99.995wt%) excluding zirconium content and gas components of carbon, oxygen and nitrogen;

said high purity hafnium having a zirconium content of 1 to 1000wtppm, an

oxygen content of 500wtppm or less, a nitrogen content of 100wtppm or

less, a carbon content of 100wtppm or less, an iron content of 10wtppm or

less, a chromium content of 10wtppm or less, and a nickel content of

10wtppm or less.

Claim 31 (new): A hafnium sputtering target according to claim 30, wherein said purity is 6N (99.9999wt%).

Claim 32 (new): A thin film formed from sputtering a hafnium sputtering target comprising:

a thin film consisting of high purity hafnium of a purity of at least 4N5

(99.995wt%) excluding zirconium content and gas components of carbon, oxygen and nitrogen;

said high purity hafnium having a zirconium content of 1 to 1000wtppm, an

oxygen content of 500wtppm or less, a nitrogen content of 100wtppm or

less, a carbon content of 100wtppm or less, an iron content of 10wtppm or

less, a chromium content of 10wtppm or less, and a nickel content of

10wtppm or less.

Claim 33 (new): A thin film according to claim 32, wherein said purity is 6N (99.9999wt%).